

INFORMATION DISCLOSURE CITATION

— 19 2001 (Use several sheets if necessary)

ATTY DOCKET NO.

97-168

SERIAL NO.

09/652,513

Shaw, et al.

FILING

August 31, 2000

GROUP

1754

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
SLA	5,160,719	11/3/92	Edler	423	344	11/4/91
SLA	5,187,129	2/16/93	Edler, et al.	501	97	7/24/90
SLA	5,230,729	7/27/93	McCandlish, et al.	75	351	12/10/92
SLA	5,275,985	1/4/94	Huang	501	97	8/23/90
SLA	5,344,634	9/6/94	Edler	423	344	11/3/92
SLA	5,405,592	4/11/95	Edler, et al.	423	344	10/20/92

RECEIVED

SEP 13 2002

TC 1700

FOREIGN PATENT DOCUMENTS

OTHER DOCUMENTS (*Including Author, Title, Date, Pertinent Pages, Etc.*)

SLU		<p>Shaw, Leon L., "Processing of Nanostructured Carbides, Nitrides, and Their Composites", Advanced Engineering Materials., Aenmfy, Vol. 2, No. 11, November, 2000, pp. 721-723</p>
SLU		<p>Shaw, Leon L., "Material Processing Via An Intergrated Mechanical and Thermal Activation Process", Materials and Manufacturing Processes, 16(3), 405-418(2001)</p>

— 10 —

W. S. Larson

DATE CONSIDERED

is (10) 0₂

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.



INFORMATION DISCLOSURE CITATION

SEP 09 2002 (use several sheets if necessary)

SEP 09 2002

ATTY DOCKET NO.

97-1681-P

SERIAL NO.

09/652,513

Shaw, et al.

FILING

August 31, 2000

GROUP

1754

U.S. PATENT DOCUMENTS

RECEIVED

SEP 13 2002

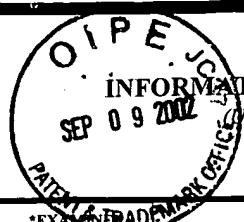
TC 1700

FOREIGN PATENT DOCUMENTS

OTHER DOCUMENTS (*Including Author, Title, Date, Pertinent Pages, Etc.*)

SUS		Ren, et al., "Synthesis of Nanostructured Silicon Carbide through an Integrated Mechanical and Thermal Activation Process", J. Am. Ceram. Soc., 85 (4) 819-27-(2002)
SUS		Shaw, et al., "Dependence of Silicon Carbide Product Morphology on the Degree of Mechanical Activation" J. Am. Ceram. Soc., 85 (3) 709-11 (2002)

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.



INFORMATION DISCLOSURE CITATION
(use several sheets if necessary)

Docket Number (Optional)

97-1681-P

Application Number

09/652,513

Applicant(s)

Shaw, et. al.

Filing Date

August 31, 2000

Group Art Unit

1754

*EXAMINER/TRADEMARK OFFICE

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

INITIAL

SLD

B.H. Kear and L.E. McCandlish, "Chemical Processing and Properties of Nanostructured WC-Co Materials," *Nanostruct. Mater.*, 3, 19-30 (1993)

SLD

P. Schwarzkopf and R. Kieffer, Refractory Hard Metals, The Macmillan Company, New York, 1953, pp. 138-161.

SLA

Jack, Engineering Applications of Ceramic Materials, ~~1984~~ **RECEIVED**
~~1984~~ ~~1984~~ ~~1984~~
SEP 13 2002

TC 1700

EXAMINER

John Wilson

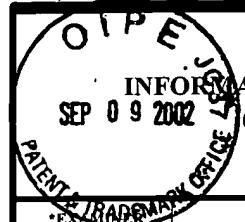
DATE CONSIDERED

10/11/02

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.



*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.



INFORMATION DISCLOSURE CITATION
SEP 09 2002

(Use several sheets if necessary)

Docket Number (Optional) 97-1681	Application Number 09/652,513
Applicant(s) Shaw, et al.	
Filing Date August 31, 2000	Group Art Unit 1754

SEP 13 2003
100
FCEIN

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

INITIAL	OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)
SLA	N.C. Angastinotis, et al. "Formation and Alloying of Nanostructured B-W Powders", NanoStructured Materials. Vol. 1 pp. 293-302, 1992
SLA	Zhu, et al. "A New Route for the Synthesis of Tungsten Carbide-Cobalt Nanocomposites" J. Am. Ceram. Soc. 77 (10) 2777-2778 (1994)
SLA	Gao, et al. "Low Temperature Carburization of High Surface Area Tungsten Powders" NanoStructured Materials, Vol. 5, pp. 555-569 (1995)
SLA	S. Mi and T.H. Courtney, "Synthesis of WC and WC-Co Cermets by Mechanical Alloying and Subsequent Hot Isostatic Pressing" Scripta Materialia, Vol. 38, No. 1. pp. 171-176, 1998
SUA	L. Gao and B.H. Kear, "Synthesis of Nanophase WC Powder by a Displacement Reaction Process," Nanostruct. Mater., 9, 205-208 (1997)
SLA	M.S. El-Eskandarany, M. Omori, M. Ishikuro, T. J. Konno, K. Takada, K. Sumiyama, T. Hirai and K. Suzuki, "Synthesis of Full-Density Nanocrystalline Tungsten Carbide by Reduction of Tungstic Oxide at Room Temperature," Metall. Mater. Trans., 27A (12) 4210-4213 (1996)
SLA	H. Mossan, "Preparation au Four Electrique de Quelques Metaux Refractaires: Tungstene, Molybdene, Vanadium", Compt. Rend., 116, 1225-1227 (1893)
SLA	P. Williams, "Sur la Preparation et les Proprietes d'un Nouveau Carbure de Tungstene", Comt. Rend., 126, 1722 (1898)
SUA	N. Pring and W. Fielding, "The Preparation at High Temperatures of some Refractory Metals from their Chlorides", J. Chem. Soc., 95, 1497-1507 (1909)
SLA	I. E. Campbell, C.F. Powell, D.H. Nowicki and B.W. Gonser, " The Vapor Phase Deposition of Refractory Materials", J. Electrochem. Soc., 96, 318 (1949)
SLA	L. Andrieux and G. Weiss, "Preparation des Composes du Molybdene et de Tungstene par Electrolyse Ignee", Bull. Soc. Chim. France, 15, 598 (1948)
SLA	P. Seegopaul, L.E. McCandlish and F.M. Shinneman "Production Capability and Powder Processing Methods for Nanostructured WC-Co Powder", Int. J. of Refractory Metals & Hard Materials 15 (1997) 133-138

EXAMINER

McCandlish

DATE CONSIDERED

10/10/02

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.